

<b>Notice of References Cited</b>	Application/Control No. 10/044,493		Applicant(s)/Patent Under Reexamination YU ET AL.	
	Examiner Kevin Quinto		Art Unit 2826	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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X	B	US-6,291,282 B1	09-2001	Wilk et al.	-
X	C	US-6,303,479 B1	10-2001	Snyder, John P.	-
X	D	US-6,590,271 B2	07-2003	Liu et al.	-
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	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Poon et al., "Thermal stability of cobalt and nickel silicides in amorphous and crystalline silicon," Proceedings of Electron Devices Meeting, 1997, IEEE, p. 65-68
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.